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| L4    | 31   | (local adj flare) and (mask or photomask) and (lithograph\$3 or photolithograph\$3) and (proximity or correction or opc) | US-PGPUB;<br>USPAT;<br>EPO;<br>DERWENT | OR               | OFF     | 2008/06/30 17:48 |
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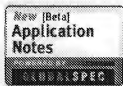
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